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ABSTRACT OF THE DISCLOSURE

MONOCRYSTALLINE SILICON SUBSTRATE COATED WITH METAL-
PLATED LAYER AND PERPENDICULAR MAGNETIC RECORDING MEDIUM

Provided is a monocrystalline Si substrate on which one or more metal films having good adhesion to the Si monocrystalline substrate are formed so that the adhesion is ensured. More specifically, provided is a surface-treated substrate comprising a monocrystalline Si substrate having volume resistivity of 1 to 100 $\Omega \cdot \text{cm}$, and at least one metal-plated layer on the monocrystalline Si substrate. The metal-plated layer which faces to the monocrystalline Si substrate preferably comprises at least one metal selected from the group consisting of Ag, Co, Cu, Ni, Pd, Fe and Pt. Furthermore, provided is a perpendicular magnetic recording medium comprising the monocrystalline Si substrate coated with the metal-plated layer.

No Figure